



US00947272B2

(12) **United States Patent**
Lee et al.

(10) **Patent No.:** **US 9,472,727 B2**
(45) **Date of Patent:** **Oct. 18, 2016**

(54) **VERTICAL STRUCTURE LEDS**

(56) **References Cited**

(71) Applicant: **LG INNOTEK CO., LTD.**, Seoul (KR)

U.S. PATENT DOCUMENTS

(72) Inventors: **Jong Lam Lee**, Kyungbuk (KR);
In-kwon Jeong, Cupertino, CA (US);
Myung Cheol Yoo, Pleasanton, CA
(US)

3,602,982 A 9/1971 Kooi
4,141,135 A 2/1979 Henry et al.
(Continued)

(73) Assignee: **LG INNOTEK CO., LTD.**, Seoul (KR)

FOREIGN PATENT DOCUMENTS

(*) Notice: Subject to any disclaimer, the term of this patent is extended or adjusted under 35 U.S.C. 154(b) by 0 days.

DE 10022879 12/2000
DE 10044500 4/2002
(Continued)

(21) Appl. No.: **14/950,773**

OTHER PUBLICATIONS

(22) Filed: **Nov. 24, 2015**

Schraud G et al: "Substrateless singlemode vertical cavity surface-emitting GaAs/GaAlAs laser diode", Electronics Letters. IEE Stevenage. GB. vo 1 • 30. No. 3. Feb. 3, 1994. pp. 238-239.

(65) **Prior Publication Data**

US 2016/0079482 A1 Mar. 17, 2016

(Continued)

Related U.S. Application Data

(60) Continuation of application No. 14/496,076, filed on Sep. 25, 2014, now Pat. No. 9,224,907, which is a continuation of application No. 14/098,185, filed on Dec. 5, 2013, now Pat. No. 8,896,017, which is a

Primary Examiner — Victor A Mandala

(74) *Attorney, Agent, or Firm* — Dentons US LLP

(Continued)

(51) **Int. Cl.**

H01L 33/00 (2010.01)

H01L 33/44 (2010.01)

(Continued)

(52) **U.S. Cl.**

CPC **H01L 33/44** (2013.01); **H01C 7/006**
(2013.01); **H01C 7/008** (2013.01);

(Continued)

(58) **Field of Classification Search**

CPC ... H01L 33/0025; H01L 33/40; H01L 33/06;
H01L 33/62; H01L 33/38; H01L 33/32;
H01L 28/20; H01L 27/0802; H01L 33/0079;
H01L 33/44; H01C 7/008; Y10S 438/977;
Y10S 438/958

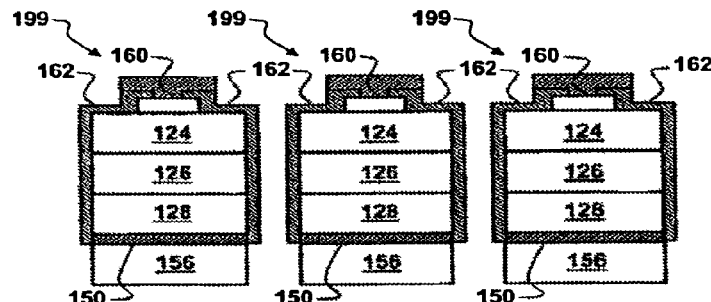
See application file for complete search history.

(57)

ABSTRACT

A vertical structure light-emitting device includes a conductive support, a light-emitting semiconductor structure disposed on the conductive support structure, the semiconductor structure having a first semiconductor surface, a side semiconductor surface and a second semiconductor surface, a first electrode electrically connected to the first-type semiconductor layer, a second electrode electrically connected to the second-type semiconductor layer, wherein the second electrode has a first electrode surface, a side electrode surface and a second electrode surface, wherein the first electrode surface, relative to the second electrode surface, is proximate to the semiconductor structure; and wherein the second electrode surface is opposite to the first electrode surface, and a passivation layer disposed on the side semiconductor surface and the second semiconductor surface.

20 Claims, 7 Drawing Sheets



6,281,526	B1 *	8/2001	Nitta	H01L 33/40 257/103
6,303,405	B1	10/2001	Yoshida et al.	
6,319,742	B1	11/2001	Hayashi et al.	
6,320,206	B1	11/2001	Coman et al.	
6,326,294	B1	12/2001	Jang et al.	
6,329,216	B1	12/2001	Matsumoto et al.	
6,335,217	B1	1/2002	Chiyo et al.	
6,339,010	B2	1/2002	Sameshima	
6,350,998	B1	2/2002	Tsuji	
6,358,770	B2	3/2002	Itoh et al.	
6,365,429	B1	4/2002	Kneissl et al.	
6,388,275	B1	5/2002	Kano	
6,410,942	B1	6/2002	Thibeault et al.	
6,426,512	B1	7/2002	Ito et al.	
6,459,712	B2	10/2002	Tanaka et al.	
6,479,836	B1	11/2002	Suzuki et al.	
6,479,839	B2	11/2002	Nikolaev et al.	
6,510,195	B1	1/2003	Chappo et al.	
6,545,296	B1	4/2003	Mukaihara et al.	
6,555,405	B2	4/2003	Chen et al.	
6,614,060	B1	9/2003	Wang et al.	
6,620,643	B1	9/2003	Koike	
6,624,491	B2	9/2003	Waitl et al.	
6,639,925	B2	10/2003	Niwa et al.	
6,677,173	B2 *	1/2004	Ota	H01S 5/32341 438/22
6,709,884	B2	3/2004	Miyazaki	
6,711,192	B1	3/2004	Chikuma et al.	
6,744,071	B2	6/2004	Sano et al.	
6,744,196	B1	6/2004	Jeon	
6,746,889	B1	6/2004	Eliashevich et al.	
6,765,232	B2	7/2004	Takahashi et al.	
6,784,463	B2	8/2004	Camras et al.	
6,791,118	B2	9/2004	Furukawa et al.	
6,800,500	B2	10/2004	Coman et al.	
6,803,603	B1	10/2004	Nitta et al.	
6,818,531	B1	11/2004	Yoo et al.	
6,846,686	B2	1/2005	Saeki et al.	
6,869,820	B2	3/2005	Chen	
6,936,488	B2	8/2005	D'Evelyn et al.	
6,954,034	B2	10/2005	Morishita	
6,955,936	B2	10/2005	Uemura et al.	
6,960,488	B2	11/2005	Brosnihan et al.	
7,084,566	B2	8/2006	Nakayama et al.	
7,109,529	B2	9/2006	Uemura et al.	
7,125,736	B2	10/2006	Morita	
7,148,520	B2	12/2006	Yoo	
7,250,638	B2	7/2007	Lee et al.	
7,496,124	B2	2/2009	Kozaki et al.	
7,569,865	B2	8/2009	Lee et al.	
7,572,478	B2	8/2009	Ogura et al.	
7,816,705	B2	10/2010	Lee et al.	
7,928,465	B2 *	4/2011	Lee	H01C 7/006 257/103
7,977,701	B2	7/2011	Hayashi et al.	
8,049,418	B2	11/2011	Yamazaki et al.	
01/0014391	A1	8/2001	Forrest et al.	
01/0019134	A1	9/2001	Chang et al.	
01/0022390	A1	9/2001	Waitl et al.	
01/0028062	A1	10/2001	Uemura et al.	
01/0042866	A1	11/2001	Coman et al.	
01/0055324	A1 *	12/2001	Ota	H01S 5/32341 372/43.01
02/0079506	A1	6/2002	Komoto et al.	
02/0081800	A1	6/2002	Morita	
02/0137244	A1	9/2002	Chen et al.	
02/0163302	A1	11/2002	Nitta et al.	
03/0143772	A1	7/2003	Chen	
04/0033638	A1	2/2004	Bader et al.	
04/0051105	A1	3/2004	Tsuda et al.	
04/0056254	A1	3/2004	Bader et al.	
04/0259279	A1	12/2004	Erchak et al.	
06/0027831	A1	2/2006	Kioke et al.	
06/0060866	A1	3/2006	Tezen	
06/0175681	A1	8/2006	Li	
06/0289886	A1	12/2006	Sakai	

(56)

References Cited**U.S. PATENT DOCUMENTS**

2007/0020790 A1 1/2007 Erchak et al.
 2007/0048885 A1 3/2007 Jeon
 2007/0122994 A1 5/2007 Sonobe et al.

FOREIGN PATENT DOCUMENTS

EP 0404565 12/1990
 EP 1168460 A2 1/2002
 GB 2346478 A 9/2000
 JP 5-304315 A 11/1993
 JP 6-302856 A 10/1994
 JP 06-302857 10/1994
 JP 0766450 A 3/1995
 JP H10-150220 6/1998
 JP 11-074560 3/1999
 JP 11-168236 6/1999
 JP 11-238913 8/1999
 JP 11-330552 11/1999
 JP 2000-077713 3/2000
 JP 2000-101139 4/2000
 JP 2000-106473 4/2000
 JP 2000-315819 11/2000
 JP 2000-323797 11/2000
 JP 2001-244503 9/2001
 JP 2001-274507 10/2001
 JP 2001-339100 12/2001
 JP 2005-522873 A 7/2005
 KR 10-2002-0000141 1/2002
 WO 01-82384 11/2001

OTHER PUBLICATIONS

Chang, K.M. et al. he silicon nitride film formed by ECR-CVD for GaN-based LED passivation, *Physica Status Solidi (a)*, Nov. 16, 2001, vol. 188, No. 1, pp. 175-178.

Stringfellow, G.B., "Organometallic Vapor Phase Epitaxy Theory and Practice", Academic Press, New York, 1989.

H. Riechert et al. "MBE Growth of (In)GaN For LED Applications", *Mater. Res. Soc. Symp. Proc.*, vol. 449 1997, pp. 149.

J. M. Van Hove et al. "GaN growth by a controllable RF-excited nitrogen source", *J. Cryst. Growth*, vol. 150, 1995, pp. 908-911.
 Johnson, M.A.L. et al. "A critical comparison between MOVPE and MBE growth of III-V nitride semiconductor materials for optoelectronic device applications" 1999, Symposium, 5.10/6 pp.
 K. Doverspike et al. "Status of nitride based light emitting and laser diodes on SiC", *Mater. Res. Soc. Symp. Proc.*, vol. 482, 1998, pp. 1169.

M.A. Herman and H. Sitter, "Molecular Beam Epitaxy Fundamentals and Current Status", Springer-Verlag, New York, 1996.

M.A.L. Johnson et al. "MBE Growth of III-V Nitride Films and Quantum well structure using multiple RF plasma sources", *Mater. Res. Soc. Symp. Proc.*, vol. 449, 1997, pp. 271.

M.K. Kelly, et al., Optical Process for Liftoff of Group III-nitride Films, *Physica Status Solidi (a)* vol. 159, 1997, pp. R3-R4.

Michael Kneissl, et al. "Continuous-Wave Operation of InGaN Multiple-Quantum-Well Laser Diodes on Copper Substrates Obtained by Laser Liftoff", *IEEE Journal on Selected Topics in Quantum Electronics*, Mar./Apr. 2001, vol. 7, No. 2, pp. 188-191.
 S. Nakamura and G. Fasol, "The Blue Laser Diode", Chapter 10, *InGaN Single-Quantum-Well Leds*, Springer-Verlag, New York., 1996.

S. Pearton, "GaN and Related Materials", Gordon and Breach Science Publishers, Netherlands, 1997.

Song Y-K, et al. "A Vertical Injection Blue Light Emitting Diode in Substrate Separated InGaN Heterostructures", *Appl. Phys. Lett.*, vol. 74, No. 24, Jun. 14, 1999, pp. 3720-3722.

W.C. Hughes et al., "Molecular beam epitaxy growth and properties of GaN films on GaN/SiC substrates", *J. Vac. Sci. Technol.*, B 13 1995, pp. 1571.

William S. Wong, et al., "Continuous-Wave InGaN Multiple-Quantum-Well Laser Diodes on Copper Substrates", *Applied Physics Letters* vol. 78, No. 9, Feb. 26, 2001; pp. 1198-1200.

William S. Wong, et al., "The integration of InxGa1-xN Multiple-Quantum-Well Laser Diodes with Copper Substrates by Laser Lift-Off", *Jpn. J. Appl. Phys.* vol. 39 (2000) pp. L 1203-L 1205, Part 2, No. 12A, Dec. 1, 2000; pp. L1203-L1205.

Wong, et al., "Integration of InGaN Laser Diodes with Dissimilar Substrates by Laser Lift-Off", *Materials Research Society*, vol. 639, 2001 pp. G12.2.1-G12.2.5.

Japanese Office Action (Appln. No. 2015-076060), May 25, 2016.

* cited by examiner

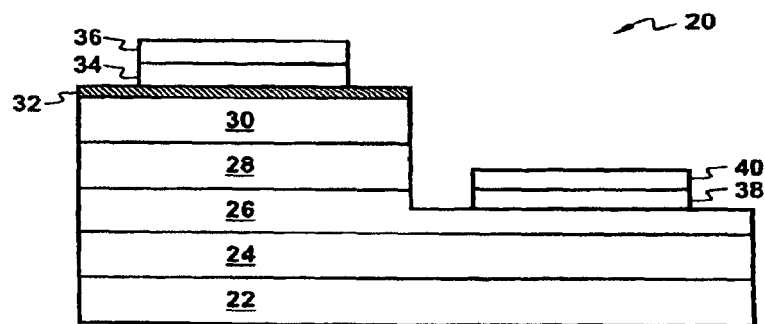


Figure 1A

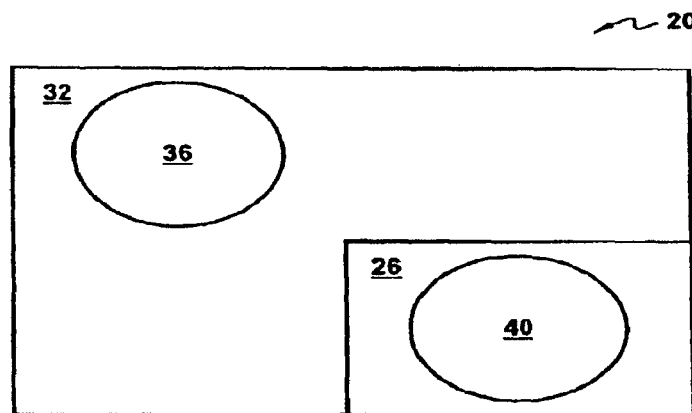


Figure 1B

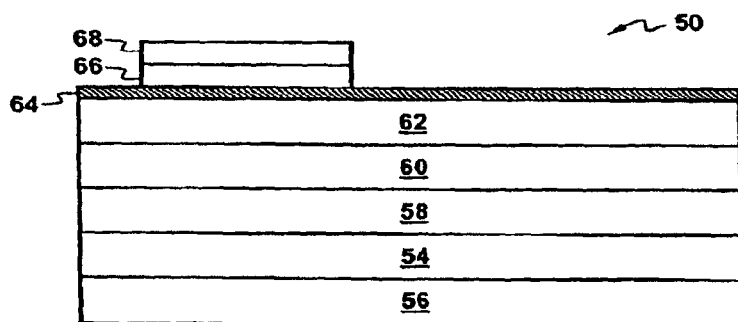


Figure 2A

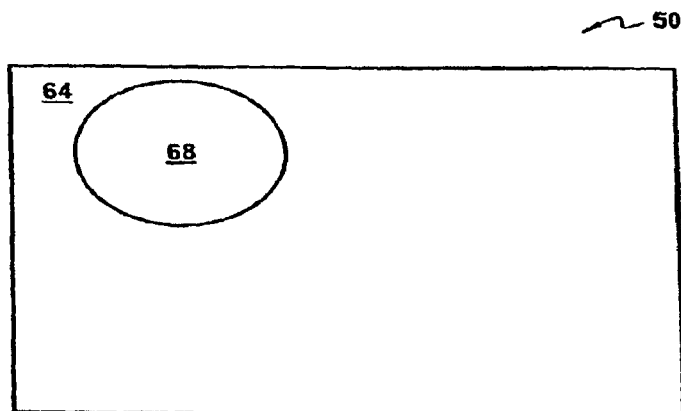


Figure 2B

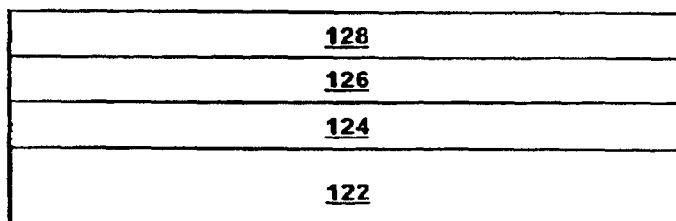


Figure 3

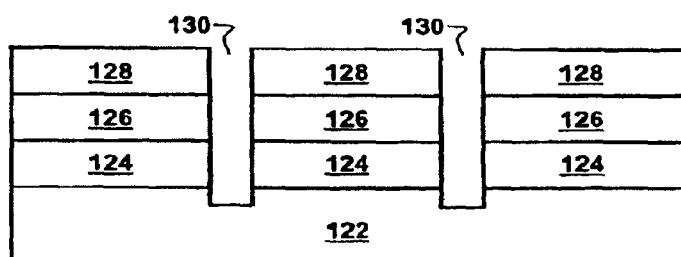


Figure 4

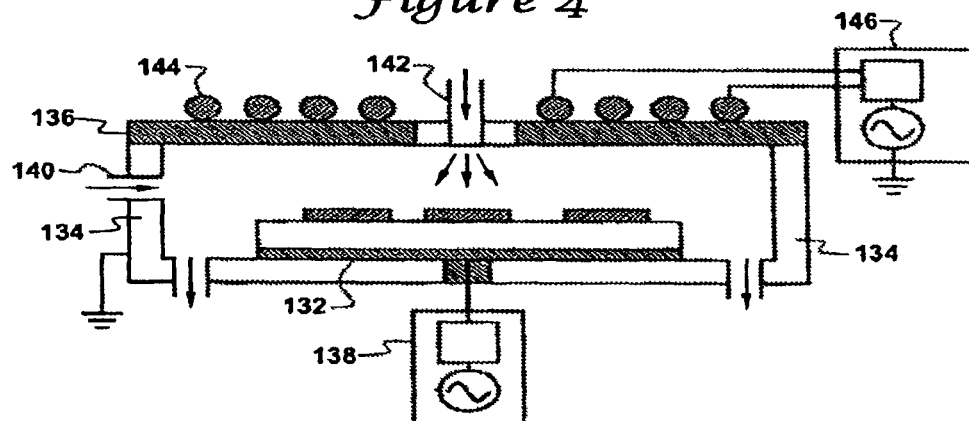


Figure 5

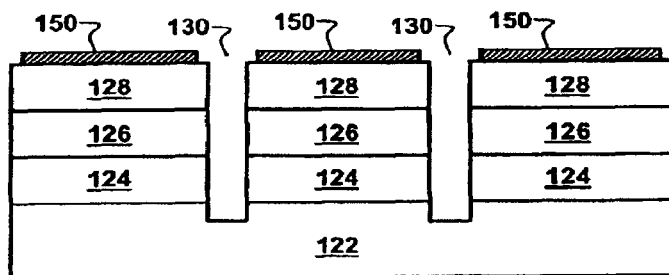


Figure 6

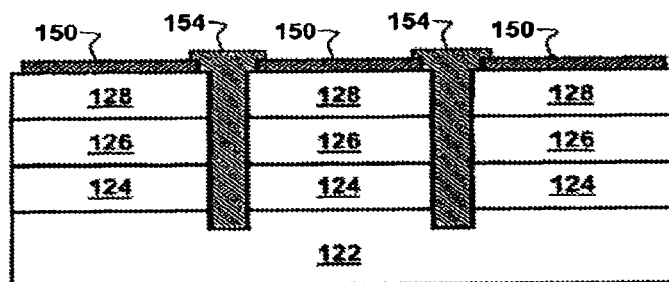


Figure 7

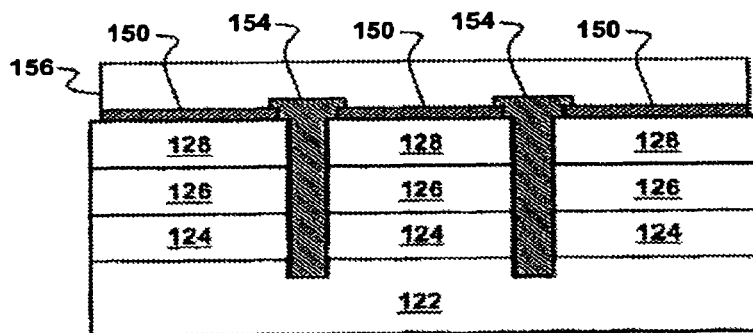


Figure 8

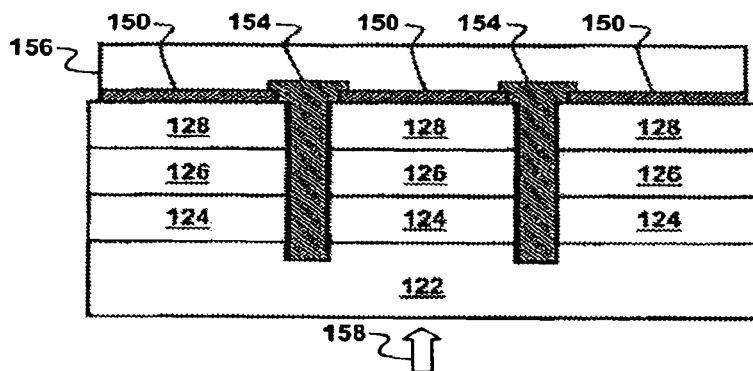


Figure 9

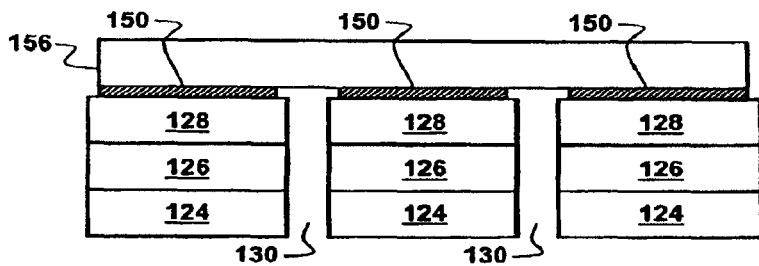


Figure 10

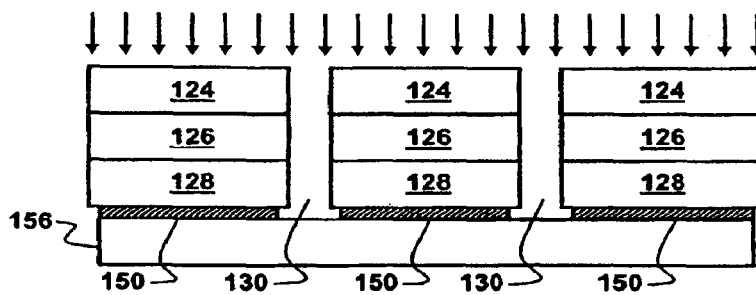


Figure 11

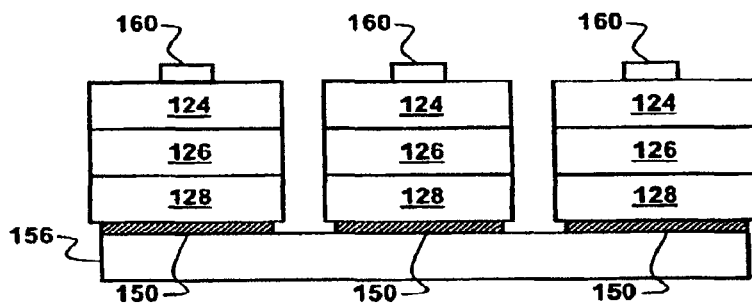


Figure 12

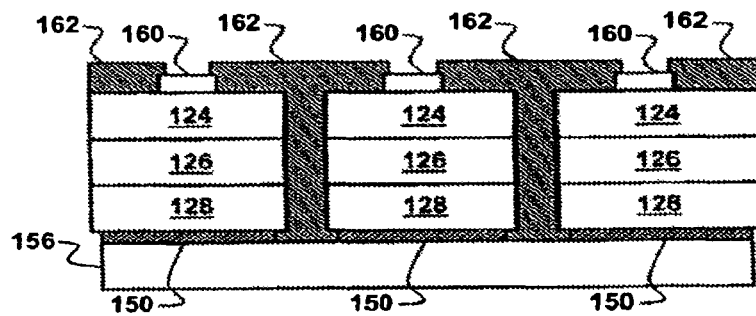


Figure 13

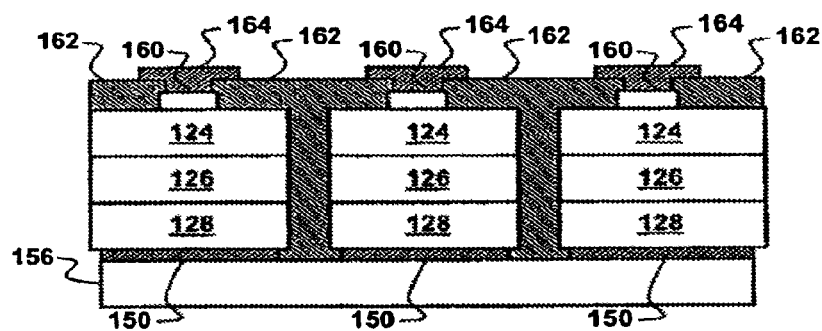


Figure 14

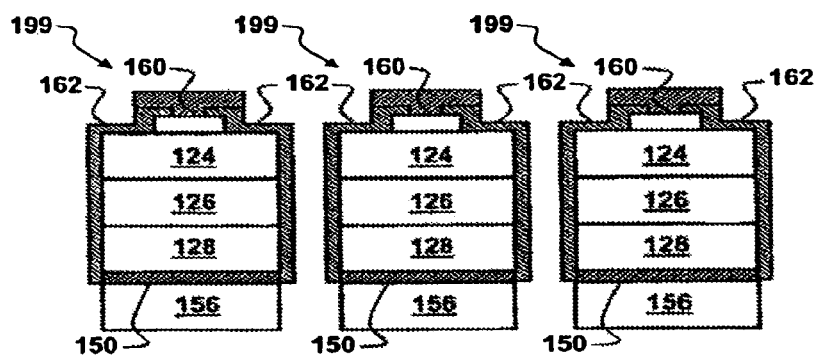


Figure 15

VERTICAL STRUCTURE LEDS

This application is a continuation application and claims benefit of U.S. patent application Ser. No. 14/496,076 filed Sep. 25, 2014, now U.S. Pat. No. 9,224,017, which is a continuation application and claims benefit of U.S. patent application Ser. No. 14/098,185 filed Dec. 5, 2013, now U.S. Pat. No. 8,896,017, which is a continuation of U.S. patent application Ser. No. 13/750,376 filed Jan. 25, 2013, now U.S. Pat. No. 8,809,898, which is a continuation of U.S. patent application Ser. No. 13/047,371 filed Mar. 14, 2011, now U.S. Pat. No. 8,384,120, which is a continuation of U.S. patent application No. 12/797,335 filed Jun. 9, 2010, now U.S. Pat. No. 7,928,465, which is a continuation of U.S. patent application Ser. No. 12/458,703 filed Jul. 21, 2009, now U.S. Pat. No. 7,816,705, which is a continuation application of U.S. patent application Ser. No. 11/002,413 filed Dec. 3, 2004, now U.S. Pat. No. 7,569,865, which is a divisional of U.S. patent application Ser. No. 10/118,316, filed Apr. 9, 2002, which are all hereby incorporated by reference in their entirety for all purposes as if fully set forth herein.

BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to semiconductor device fabrication. More particularly, the present invention relates to a method of fabricating vertical devices using a metal support layer.

2. Discussion of the Related Art

Light emitting diodes ("LEDs") are well-known semiconductor devices that convert electrical current into light. The color (wavelength) of the light that is emitted by an LED depends on the semiconductor material that is used to fabricate the LED. This is because the wavelength of the emitted light depends on the semiconductor material's band-gap, which represents the energy difference between the material's valence band and conduction band electrons.

Gallium-Nitride (GaN) has gained much attention from LED researchers. One reason for this is that GaN can be combined with indium to produce InGaN/GaN semiconductor layers that emit green, blue, and white light. This wavelength control ability enables an LED semiconductor designer to tailor material characteristics to achieve beneficial device characteristics. For example, GaN enables an LED semiconductor designer to produce blue LEDs, which are beneficial in optical recordings, and white LEDs, which can replace incandescent lamps.

Because of the foregoing and other advantageous, the market for GaN-based LEDs is rapidly growing. Accordingly, GaN-based opto-electronic device technology has rapidly evolved since their commercial introduction in 1994. Because the efficiency of GaN light emitting diodes has surpassed that of incandescent lighting, and is now comparable with that of fluorescent lighting, the market for GaN based LEDs is expected to continue its rapid growth.

Despite the rapid development of GaN device technology, GaN devices are too expensive for many applications. One reason for this is the high cost of manufacturing GaN-based devices, which in turn is related to the difficulties of growing GaN epitaxial layers and of subsequently dicing out completed GaN-based devices.

GaN-based devices are typically fabricated on sapphire substrates. This is because sapphire wafers are commercially available in dimensions that are suitable for mass-producing GaN-based devices, because sapphire supports relatively

high-quality GaN epitaxial layer growths, and because of the extensive temperature handling capability of sapphire.

Typically, GaN-based devices are fabricated on 2" diameter sapphire wafers that are either 330 or 430 microns thick. Such a diameter enables the fabrication of thousands of individual devices, while the thickness is sufficient to support device fabrication without excessive wafer warping. Furthermore, sapphire is chemically and thermally stable, has a high melting temperature that enables high temperature fabrication processes, has a high bonding energy (122.4 Kcal/mole), and a high dielectric constant. Chemically, sapphires are crystalline aluminum oxide, Al_2O_3 .

Fabricating semiconductor devices on sapphire is typically performed by growing an n-GaN epitaxial layer on a sapphire substrate using metal oxide chemical vapor deposition (MOCVD) or molecular beam epitaxy (MBE). Then, a plurality of individual devices, such as GaN LEDs, is fabricated on the epitaxial layer using normal semiconductor processing techniques. After the individual devices are fabricated they must be diced out (separated) of the sapphire substrate. However, since sapphires are extremely hard, are chemically resistant, and do not have natural cleave angles, sapphire substrates are difficult to dice. Indeed, dicing typically requires that the sapphire substrate be thinned to about 100 microns by mechanical grinding, lapping, and/or polishing. It should be noted that such mechanical steps are time consuming and expensive, and that such steps reduce device yields. Even after thinning sapphires remain difficult to dice. Thus, after thinning and polishing, the sapphire substrate is usually attached to a supporting tape. Then, a diamond saw or stylus forms scribe lines between the individual devices. Such scribing typically requires at least half an hour to process one substrate, adding even more to the manufacturing costs. Additionally, since the scribe lines have to be relatively wide to enable subsequent dicing, the device yields are reduced, adding even more to manufacturing costs. After scribing, the sapphire substrates can be rolled using a rubber roller or struck with a knife-edge to produce stress cracks that can be used to dice out the individual semiconductor devices. Such mechanical handling reduces yields even more.

Of note, because sapphire is an insulator the LED device topologies that are available when using sapphire substrates (or other insulating substrates) are, in practice, limited to lateral and vertical topologies. In the lateral topology the metallic electrical contacts that are used to inject electrical current into the LED are both located on upper surfaces (or on the same side of the substrate). In the vertical topology one metallic contact is on an upper surface, the sapphire (insulating) substrate is removed, and the other contact is located on a lower surface.

FIGS. 1A and 1B illustrate a typical lateral GaN-based LED 20 that is fabricated on a sapphire substrate 22. Referring now specifically to FIG. 1A, an n-GaN buffer layer 24 is formed on the substrate 22. A relatively thick n-GaN layer 26 is formed on the buffer layer 24. An active layer 28 having multiple quantum wells of aluminum-indium-gallium-nitride (AlInGaN) or of InGaN/GaN is then formed on the n-type GaN layer 26. A p-GaN layer 30 is then formed on the active layer 26. A transparent conductive layer 32 is then formed on the p-GaN layer 30. The transparent conductive layer 32 may be made of any suitable material, such as Ru/Au, Ni/Au or indium-tin-oxide (ITO). A p-type electrode 34 is then formed on one side of the transparent conductive layer 32. Suitable p-type electrode materials include Ni/Au, Pd/Au, Pd/Ni and Pt. A pad 36 is then formed on the p-type electrode 34. Beneficially, the pad 36 is Au.

The transparent conductive layer **32**, the p-GaN layer **30**, the active layer **28** and part of the n-GaN layer **26** are etched to form a step. Because of the difficulty of wet etching GaN, a dry etch is usually used. This etching requires additional lithography and stripping processes. Furthermore, plasma damage to the GaN step surface is often sustained during the dry-etch process. The LED **20** is completed by forming an n-electrode pad **38** (usually Au) and a pad **40** on the step.

FIG. 1B illustrates a top down view of the LED **20**. As can be seen, lateral GaN-based LEDs have a significant drawback in that having both metal contacts (**36** and **40**) on the same side of the LED significantly reduces the surface area available for light emission. As shown in FIG. 1B the metal contacts **36** and **40** are physically close together. Furthermore, as previously mentioned the pads **36** are often Au. When external wire bonds are attached to the pads **36** and **40**, the Au often spreads. Au spreading can bring the electrical contacts even closer together. Such closely spaced electrodes **34** are highly susceptible to ESD damage.

FIGS. 2A and 2B illustrate a vertical GaN-based LED **50** that was formed on a sapphire substrate that was subsequently removed. Referring now specifically to FIG. 2A, the LED **50** includes a GaN buffer layer **54** having an n-metal contact **56** on a bottom side, and a relatively thick n-GaN layer **58** on the other. The n-metal contact **56** is beneficially formed from a high reflectivity layer that is overlaid by a high conductivity metal, including, for example, Au. An active layer **60** having multiple quantum wells is formed on the n-type GaN layer **58**, and a p-GaN layer **62** is formed on the active layer **60**. A transparent conductive layer **64** is then formed on the p-GaN layer **62**, and a p-type electrode **66** is formed on the transparent conductive layer **64**. A pad **68** is formed on the p-type electrode **66**. The materials for the various layers are similar to those used in the lateral LED **20**. The vertical GaN-based LED **50** as the advantage that etching a step is not required. However, to locate the n-metal contact **56** below the GaN buffer layer **54** the sapphire substrate (not shown) has to be removed. Such removal can be difficult, particularly if device yields are of concern. However, as discussed subsequently, sapphire substrate removal using laser lift off is known.

Referring now to FIG. 2B, vertical GaN-based LEDs have the advantage that only one metal contact (**68**) blocks light. Thus, to provide the same amount of light emission area, lateral GaN-based LEDs must have a larger surface area, which lowers device yields. Furthermore, the reflecting layer of the n-type contact **56** of vertical GaN-based LEDs reflect light that is otherwise absorbed in lateral GaN-based LEDs. Thus, to emit the same amount of light as a vertical GaN-based LED, a lateral GaN-based LED must have a significantly larger surface area. Because of these issues, a 2" diameter sapphire wafer can produce about 35,000 vertical GaN-based LEDs, but only about 12,000 lateral GaN-based LEDs. Furthermore, the lateral topology is more vulnerable to static electricity, primarily because the two electrodes (**36** and **40**) are so close together. Additionally, as the lateral topology is fabricated on an insulating substrate, and as the vertical topology can be attached to a heat sink, the lateral topology has relatively poor thermal dissipation. Thus, in many respects the vertical topology is operationally superior to the lateral topology.

However, most GaN-based LEDs fabricated with a lateral topology. This is primarily because of the difficulties of removing the insulating substrate and of handling the GaN wafer structure without a supporting substrate. Despite these problems, removal of an insulation (growth) substrate and subsequent wafer bonding of the resulting GaN-based wafer

on a Si substrate using Pd/In metal layers has been demonstrated for very small area wafers, approx. 1 cm by 1 cm. But, substrate removal and subsequent wafer bonding of large area wafers remains very difficult due to inhomogeneous bonding between the GaN wafer and the 2nd (substitutional) substrate. This is mainly due to wafer bowing during and after laser lift off.

Thus, it is apparent that a new method of fabricating vertical topology devices would be beneficial. In particular, a method that provides for mechanical stability of semiconductor wafer layers, that enables vertical topology electrical contact formation, and that improves heat dissipation would be highly useful, particularly with devices subject to high electrical currents, such as laser diodes or high-power LEDs. Beneficially, such a method would enable forming multiple semiconductor layers on an insulating substrate, the adding of a top support metal layer that provides for top electrical contacts and for structural stability, and the removal of the insulating substrate. Of particular benefit would be a new method of forming partially fabricated semiconductor devices on a sapphire (or other insulating) substrate, the adding of a top support metal layer over the partially fabricated semiconductor layers, the removal of the sapphire (or other insulating) substrate, the formation of bottom electrical contacts, and the dicing of the top support metal layer to yield a plurality of devices. Specifically advantageous would be fabrication process that produces vertical topology GaN-based LEDs.

SUMMARY OF THE INVENTION

The following summary of the invention is provided to facilitate an understanding of some of the innovative features unique to the present invention, and is not intended to be a full description. A full appreciation of the various aspects of the invention can be gained by taking the entire specification, claims, drawings, and abstract as a whole.

The principles of the present invention provide for a method of fabricating semiconductor devices on insulating substrates by first forming semiconductor layers on the insulating substrate, followed by forming a metal layer over the semiconductor layers, followed by removal of the insulating substrate to isolate a structurally supported wafer comprised of the formed semiconductor layers and the metal layer. The metal layer supports the semiconductor layers to prevent warping and/or other damage and provides for electrical contacts. Beneficially, the metal layer includes a metal, such as Cu, Cr, Ni, Au, Ag, Mo, Pt, Pd, W, or Al, or a metal containing material such as titanium nitride. Forming of the metal layer can be performed in numerous ways, for example, by electroplating, by electro-less plating, by CVD, or by sputtering. Subsequently, bottom electrical contacts can be added to the semiconductor layers and then individual semiconductor devices can be diced from the resulting structure.

The principles of the present invention further provide for a method of fabricating vertical topology GaN-based devices on an insulating substrate by the use of a metal support film and by the subsequent removal of the insulating substrate. According to that method, semiconductor layers for the GaN-based devices are formed on an insulating (sapphire) substrate using normal semiconductor fabrication techniques. Then, trenches that define the boundaries of the individual devices are formed through the semiconductor layers. Those trenches may also be formed into the insulating substrate. Trench forming is beneficially performed using inductive coupled plasma reactive ion etching (ICP-

5

RIE). The trenches are then filled with an easily removed layer (such as a photo-resist). A metal support structure is then formed on the semiconductor layers. Beneficially, the metal support structure includes a metal, such as Cu, Cr, Ni, Au, Ag, Mo, Pt, Pd, W, or Al, or a metal-containing material such as titanium nitride. Forming of the metal support structure can be performed in numerous ways, for example, by electroplating, by electro-less plating, by CVD, or by sputtering. The insulating substrate is then removed, beneficially using a laser-lift off process. Electrical contacts, a passivation layer, and metallic pads are then added to the individual devices, and the individual devices are then diced out.

The principles of the present invention specifically provide for a method of fabricating vertical topology GaN-based LEDs on sapphire substrates. According to that method, semiconductor layers for the vertical topology GaN-based LEDs are formed on a sapphire substrate using normal semiconductor fabrication techniques. Then, trenches that define the boundaries of the individual vertical topology GaN-based LEDs are formed through the semiconductor layers. Those trenches may also be formed into the sapphire substrate. Trench forming is beneficially performed using inductive coupled plasma reactive ion etching (ICP/RIE). Beneficially, the trenches are fabricated using ICP/RIE. The trenches are then beneficially filled with an easily removed layer (such as a photo-resist). A metal support structure is then formed on the semiconductor layers. Beneficially, the metal support structure includes a metal, such as Cu, Cr, Ni, Au, Ag, Mo, Pt, Pd, W, or Al, or a metal-containing material such as titanium nitride. Forming of the metal layer can be performed in numerous ways, for example, by electroplating, by electro-less plating, by CVD, or by sputtering. The sapphire substrate is then removed, beneficially using a laser-lift off process. Electrical contacts, a passivation layer, and metallic pads are then added to the individual LEDs, and the individual LEDs are then diced out.

The novel features of the present invention will become apparent to those of skill in the art upon examination of the following detailed description of the invention or can be learned by practice of the present invention. It should be understood, however, that the detailed description of the invention and the specific examples presented, while indicating certain embodiments of the present invention, are provided for illustration purposes only because various changes and modifications within the spirit and scope of the invention will become apparent to those of skill in the art from the detailed description of the invention and claims that follow.

BRIEF DESCRIPTION OF THE DRAWINGS

The accompanying figures, in which like reference numerals refer to identical or functionally-similar elements throughout the separate views and which are incorporated in and form part of the specification, further illustrate the present invention and, together with the detailed description of the invention, serve to explain the principles of the present invention.

In the drawings:

FIG. 1A illustrates a sectional view of a typical lateral topology GaN-based LED;

FIG. 1B shows a top down view of the GaN-based LED illustrated in FIG. 1A;

FIG. 2A illustrates a sectional view of a typical vertical topology GaN-based LED;

6

FIG. 2B shows a top down view of the GaN-based LED illustrated in FIG. 2A; and

FIGS. 3-15 illustrate steps of forming a light emitting diode that are in accord with the principles of the present invention.

DETAILED DESCRIPTION OF THE ILLUSTRATED EMBODIMENTS

The principles of the present invention provide for methods of fabricating semiconductor devices, such as GaN-based vertical topology LEDs, on insulating substrates, such as sapphire substrates, using metal support films. While those principles are illustrated in a detailed description of a method of fabricating vertical topology GaN-based LEDs on a sapphire substrate, those principles are broader than that illustrated method. Therefore, the principles of the present invention are to be limited only by the appended claims as understood under United States Patent Laws.

FIGS. 3-15 illustrate a method of manufacturing vertical topology GaN-based light emitting diodes (LEDs) on sapphire substrates. Sapphire substrates are readily available in suitable sizes, are thermally, chemically, and mechanically stable, are relatively inexpensive, and support the growth of good quality GaN epitaxial layers. It should be understood that those figures are not to scale.

Referring now to FIG. 3, initially a GaN-based LED layer structure is formed on a 330-430 micron-thick, 2" diameter (0001) sapphire substrate **122**. The GaN-based LED layer structure includes an n-GaN buffer layer **124**, an InGaN/GaN active layer **126** (beneficially having the proper composition to emit blue light) on the buffer layer **124**, and a p-GaN contact layer **128** on the active layer **126**.

Still referring to FIG. 3, the buffer layer **124** beneficially includes both a 2 μ m undoped GaN layer formed directly on the substrate, and a 1 μ m thick, n-type, silicon doped, GaN layer. The p-GaN contact layer **128** is beneficially about 0.05 μ m thick and is doped with Mg. Overall, the GaN-based LED layer structure is beneficially less than about 5 microns thick. Various standard epitaxial growth techniques, such as vapor phase epitaxy, MOCVD, and MBE, together with suitable dopants and other materials, can be used to produce the GaN-based LED layer structure.

Referring now to FIG. 4, trenches **130** are formed through the vertical topology GaN-based LED layer structure. Those trenches **130** may extend into the sapphire substrate **122**. The trenches **130** define the individual LED semiconductor structures that will be produced. Each individual LED semiconductor structure is beneficially a square about 200 microns wide. The trenches **130** are beneficially narrower than about 10 microns (preferably close to 1 micron) and extend deeper than about 5 microns into the sapphire substrate **122**. The trenches **130** assist a subsequent chip separation process.

Because of the hardness of sapphire and GaN, the trenches **130** are beneficially formed in the structure of FIG. 3 using reactive ion etching, preferably inductively coupled plasma reactive ion etching (ICP RIE). Forming trenches using ICP RIE has two main steps: forming scribe lines and etching. Scribe lines are formed on the structure of FIG. 3 using a photo-resist pattern in which areas of the sapphire substrate **122** where the trenches **130** are to be formed are exposed. The exposed areas are the scribe lines, while all other areas are covered by photo-resist. The photo-resist pattern is beneficially fabricated from a relatively hard photo-resist material that withstands intense plasma. For

example, the photo-resist could be AZ 9260, while the developer used to develop the photo-resist to form the scribe lines could be AZ MIF 500.

In the illustrated example, the photo-resist is beneficially spin coated to a thickness of about 10 microns. However, in general, the photo-resist thickness should be about the same as the thickness of the vertical topology GaN-based LED layer structure plus the etch depth into the sapphire substrate **122**. This helps ensure that the photo-resist mask remains intact during etching. Because it is difficult to form a thick photo-resist coating in one step, the photo-resist can be applied in two coats, each about 5 microns thick. The first photo-resist coat is spin coated on and then soft baked, for example, at 90° F. for about 15 minutes. Then, the second photo-resist coat is applied in a similar manner, but is soft baked, for example, at 110° F. for about 8 minutes. The photo-resist coating is then patterned to form the scribe lines. This is beneficially performed using lithographic techniques and development. Development takes a relatively long time because of the thickness of the photo-resist coating. After development, the photo-resist pattern is hard baked, for example, at about 80° F. for about 30 minutes. Then, the hard baked photo-resist is beneficially dipped in a MCB (Metal Chlorobenzene) treatment for about 3.5 minutes. Such dipping further hardens the photo-resist.

After the scribe lines are defined, the structure of FIG. 3 is etched. Referring now to FIG. 5, the ICP RIE etch process is performed by placing the structure of FIG. 3 on a bottom electrode **132** in a RIE chamber **134** having an insulating window **136** (beneficially a 1 cm-thick quartz window). The bottom electrode **132** is connected to a bias voltage supply **138** that biases the structure of FIG. 3 to enable etching. The bias voltage supply **138** beneficially supplies 13.56 MHz RF power and a DC-bias voltage. The distance from the insulating window **136** to the bottom electrode **132** is beneficially about 6.5 cm. A gas mixture of Cl₂ and BCl₃, and possibly Ar, is injected into the RIE chamber **134** through a reactive gas port **140**. Furthermore, electrons are injected into the chamber via a port **142**. A 2.5-turn or so spiral Cu coil **144** is located above the insulating window **136**. Radio frequency (RF) power at 13.56 MHz is applied to the coil **144** from an RF source **146**. It should be noted that magnetic fields are produced at right angles to the insulating window **136** by the RF power.

Still referring to FIG. 5, electrons present in the electromagnetic field produced by the coil **144** collide with neutral particles of the injected gases, resulting in the formation of ions and neutrals, which produce plasma. Ions in the plasma are accelerated toward the structure of FIG. 3 by the bias voltage applied by the bias voltage supply **138** to the bottom electrode **132**. The accelerated ions pass through the scribe lines, forming the etch channels **130** (see FIG. 4).

Referring now to FIG. 6, after the trenches **130** are formed, thin p-contacts **150** are formed on the individual LED semiconductor structures of the GaN-based LED layer structure. Those contacts **150** are beneficially comprised of Pt/Au, Pd/Au, Ru/Au, Ni/Au, Cr/Au, or of indium tin oxide (ITO)/Au and are less than 10 nm. Such contacts can be formed using a vacuum evaporator (electron beam, thermal, sputter), followed by thermal annealing at an intermediate temperature (approximately 300-700° C.).

As shown in FIG. 7, after the contacts **150** are formed, the trenches **130** are filled with an easily removed material (beneficially a photo-resist) to form posts **154**.

Referring now to FIG. 8, after the posts **154** are formed, a metal support layer **156** approximately 50 μm is formed over the posts **154** and over the p-contacts **150**. The posts

154 prevent the metal that forms the metal support layer **156** from entering into the trenches. The metal support layer **156** is beneficially comprised of a metal having good electrical and thermal conductivity and that is easily formed, such as by electroplating, by electro-less plating, by CVD, or by sputtering. Before electroplating or electro-less plating, it is beneficial to coat the surface with a suitable metal, such as by sputtering. For example, the metal support layer **156** can be Cu, Cr, Ni, Au, Ag, Mo, Pt, Pd, W, or Al. Alternatively, the metal support layer **156** can be comprised of a metal-containing material such as titanium nitride.

Turning now to FIG. 9, the sapphire substrate **122** is then removed from the remainder of the structure using light **158** from an eximer laser (having a wavelength less than 350 nanometers), while the sapphire substrate is biased away from the remainder of the structure (such as by use of vacuum chucks). The laser beam **158** passes through the sapphire substrate **122**, causing localized heating at the junction of the sapphire substrate **122** and the n-GaN buffer layer **124**. That heat decomposes the GaN at the interface of the sapphire substrate, which, together with the bias, causes the sapphire substrate **122** to separate, reference FIG. 10. It is beneficial to hold the other side of the structure with a vacuum chuck during laser lift off. This enable easy application of a separation bias.

Laser lift off processes are described in U.S. Pat. No. 6,071,795 to Cheung et al., entitled, "Separation of Thin Films From Transparent Substrates By Selective Optical Processing," issued on Jun. 6, 2000, and in Kelly et al. "Optical process for liftoff of group III-nitride films", Physica Status Solidi (a) vol. 159, 1997, pp. R3-R4. Beneficially, the metal support layer **156** fully supports the individual LED semiconductor structures during and after separation of the sapphire substrate.

Still referring to FIG. 10, the posts **154** are then removed, leaving the trenches **130** behind.

Turning now to FIG. 11, the structure of FIG. 10 is inverted. Then, the side opposite the metal support layer **156** is cleaned with HCl to remove Ga droplets (laser beam **158** heating separates GaN into Ga+N). After cleaning, ICP RIE polishing (using Cl₂ and/or Cl₂+BCl₃) is performed to smooth the exposed surface (which is rough due to the separation of the sapphire substrate). Polishing produces an atomically flat surface of pure n-GaN on the n-GaN buffer layer **124**.

Turning now to FIG. 12, n-type ohmic contacts **160** are formed on the n-GaN buffer layer **124** using normal semiconductor-processing techniques. Beneficially, the n-type ohmic contacts **160** are comprised of Ti/Al-related materials.

Turning now to FIG. 13, to protect the semiconductor layers from subsequent processing, a passivation layer **162** is formed on the n-type ohmic contacts **160** and in the trenches **130**. Electrical insulation comprised of SiO₂ or Si₃N₄ are suitable passivation layer materials. Additionally, as shown, the passivation layer **162** is patterned to expose top surface portions of the n-type ohmic contacts **160**.

Turning now to FIG. 14, after the passivation layer **162** is formed, metal pads **164** are formed on the n-type ohmic contacts **160**. As shown in FIG. 14, the metal pads **164** extend over portions of the passivation layer **162**. The metal pads **164** are beneficially comprised of Cr and Au.

After the metal pads **164** are formed, individual devices can be diced out. Referring now to FIG. 15, dicing is beneficially accomplished using photolithographic techniques to etch through the metal support layer **156** to the bottom of the passivation layer **162** (at the bottom of the trenches **130**) and by removal of the passivation layer **162**. Alternatively, sawing can be used. In practice, it is probably

better to perform sawing at less than about 0° C. The result is a plurality of vertical topology GaN LEDs **199** on conductive substrates.

The foregoing has described forming trenches **130** before laser lift off of the sapphire substrate **122**. However, this is not required. The sapphire substrate **122** could be removed first, and then trenches **130** can be formed.

The embodiments and examples set forth herein are presented to best explain the present invention and its practical application and to thereby enable those skilled in the art to make and utilize the invention. Those skilled in the art, however, will recognize that the foregoing description and examples have been presented for the purpose of illustration and example only. Other variations and modifications of the present invention will be apparent to those of skill in the art, and it is the intent of the appended claims that such variations and modifications be covered. The description as set forth is not intended to be exhaustive or to limit the scope of the invention. Many modifications and variations are possible in light of the above teaching without departing from the spirit and scope of the following claims. It is contemplated that the use of the present invention can involve components having different characteristics. It is intended that the scope of the present invention be defined by the claims appended hereto, giving full cognizance to equivalents in all respects.

What is claimed is:

1. A light-emitting device, comprising:
 - a support structure of metal;
 - a GaN-based semiconductor structure on the support structure, the GaN-based semiconductor structure including a p-type GaN-based layer, a GaN-based active layer, and an n-type GaN-based layer, wherein the GaN-based semiconductor structure has a first surface, a side surface, and a second surface, wherein the first surface, relative to the second surface, is proximate to the support structure, and wherein the second surface is opposite to the first surface;
 - a p-type electrode on the support structure; and
 - an n-type electrode on the second surface of the GaN-based semiconductor structure; and
 - a passivation layer on the side surface of the GaN-based semiconductor structure, wherein the passivation layer extends from the side surface of the GaN-based semiconductor structure to cover the second surface of the GaN-based semiconductor structure and a side surface and an upper surface of the n-type electrode, and wherein a portion of the passivation layer is between the semiconductor structure and the support structure.
2. The device according to claim 1, wherein a thickness of the GaN-based semiconductor structure is 100 times or less than a thickness of the p-type GaN-based layer.

3. The device according to claim 1, wherein a thickness of the GaN-based semiconductor structure is 5 times or less than a thickness of the n-type GaN-based layer.

4. The device according to claim 1, wherein a thickness of the GaN-based semiconductor structure is 1.7 times or less than a thickness of the n-type GaN-based layer.

5. The device according to claim 1, wherein the support structure comprises Cu.

6. The device according to claim 1, wherein the GaN-based semiconductor structure is less than 5 microns thick.

7. The device according to claim 1, wherein the support structure is at least 10 times thicker than the GaN-based semiconductor structure.

8. The device according to claim 1, wherein an area of the passivation layer covering the side surface of the n-type electrode is larger than an area of the passivation layer covering the upper surface of the n-type electrode.

9. The device according to claim 1, further comprising a metal pad on the passivation layer covering the upper surface of the n-type electrode.

10. The device according to claim 9, wherein the metal pad is on the passivation layer covering the upper surface of the n-type electrode.

11. The device according to claim 1, wherein the passivation layer covering the upper surface of the n-type electrode is patterned to form an open space to expose the upper surface of the n-type electrode.

12. The device according to claim 1, wherein an area of the passivation layer covering the n-type GaN-based layer is larger than an area of the passivation layer covering the p-type GaN-based layer.

13. The device according to claim 1, wherein an area of the passivation layer covering the n-type GaN-based layer is larger than an area of the passivation layer covering the GaN-based active layer.

14. The device according to claim 1, wherein an area of the passivation layer covering the n-type GaN-based layer is larger than an area of the passivation layer covering the side surface of the n-type electrode.

15. The device according to claim 1, wherein an area of the passivation layer covering the n-type GaN-based layer is larger than an area of the passivation layer covering the upper surface of the n-type electrode.

16. The device according to claim 1, wherein the passivation layer is in contact with the support structure.

17. The device according to claim 1, wherein the support structure is thicker than the p-type GaN-based layer.

18. The device according to claim 1, wherein the support structure is thicker than the n-type GaN-based layer.

19. The device according to claim 1, wherein the support structure comprises a metal layer and metal coating layer.

20. The device according to claim 19, wherein the metal coating layer is between the metal layer and the p-type electrode.

* * * * *